

MRS Invites Nominations for the Von Hippel Award, MRS Medal, and Turnbull Lectureship

Nominations are being sought for the von Hippel Award, the MRS Medal, and the Turnbull Lectureship. These awards will be presented at the 1995 MRS Fall Meeting, November 27–December 1, in Boston.

The MRS Awards Program recognizes outstanding contributors to the progress of materials research. Nomination forms and details about eligibility and nomination criteria are available from Anne Wagner, Materials Research Society, 9800 McKnight Road, Pittsburgh, PA 15237-6006; phone 412-367-3003; fax 412-367-4373.

Von Hippel Award Acknowledges Outstanding Interdisciplinary Work in Materials Research

The Von Hippel Award, first presented to Arthur R. von Hippel whose interdisciplinary and pioneering research typified the spirit of the award, is the Materials Research Society's highest honor. The recipient is recognized for brilliance and originality combined with vision that tran-

scends the boundaries of conventional scientific disciplines. The Award includes a \$7,500 cash prize, honorary membership of MRS, and a unique trophy—a mounted ruby laser crystal symbolizing the many-faceted nature of materials research.

Selection of the recipient is determined by a vote of the MRS Council. The recipient will be invited to speak at the Awards Ceremony.

MRS Medal Recognizes Recent Discovery or Advancement in Materials Science

The MRS Medal offers public and professional recognition of an exceptional recent achievement in materials research. A Medal will be awarded for a specific outstanding recent discovery or advancement which is expected to have a major impact on the progress of any materials-related field.

The Award consists of a \$2,000 cash prize, an engraved and mounted Medal, and a citation certificate.

Turnbull Lectureship Honors Career of an Outstanding Researcher and Communicator

The David Turnbull Lectureship recognizes the career of a scientist who has made outstanding contributions to understanding materials phenomena and properties through research, writing, and lecturing, as exemplified by the life work of David Turnbull. While honoring the accomplishments of the recipient, the Turnbull Lectureship is intended to support and enrich the materials research community.

The recipient will give a technical lecture of broad appeal at a designated session of the 1995 MRS Fall Meeting. The Turnbull Lecturer will receive a \$3,000 honorarium and a citation plaque, along with travel expenses paid to enable the recipient to address MRS Sections and University Chapters, and/or participate in production of a video version of the lecture.

Previous Recipients of the von Hippel Award

Arthur R. von Hippel

Massachusetts Institute of Technology

William O. Baker

AT&T Bell Laboratories

David Turnbull

Harvard University

W. Conyers Herring

Stanford University

James W. Mayer

Cornell University

Clarence M. Zener

Carnegie-Mellon University

Sir Peter B. Hirsch

University of Oxford

Walter L. Brown

AT&T Bell Laboratories

John W. Cahn

National Bureau of Standards

Minko Balkanski

Universite Pierre et Marie Curie

Sir Charles Frank

University of Bristol

Jacques Friedel

Universite de Paris-Sud

John B. Goodenough

University of Texas—Austin

Robert W. Balluffi

Massachusetts Institute of Technology

Theodore H. Geballe

Stanford University

Michael F. Ashby

Cambridge University

Alfred Y. Cho

AT&T Bell Laboratories

Recent Recipients of the MRS Medal

Arthur J. Freeman

Northwestern University

Duward F. Shriver

Northwestern University

Bernard S. Meyerson

IBM

Shigeyuki Somiya

Nishi Tokyo University

L. Eric Cross

The Pennsylvania State University

Stephen J. Pennycook

Oak Ridge National Laboratory

Wolfgang Krätschmer

Max-Planck Institut für Kemphysik

Donald R. Huffman

University of Arizona

Max G. Legally

University of Wisconsin—Madison

Kenneth S. Suslick

University of Illinois at Urbana-Champaign

Previous Recipients of the Turnbull Lectureship

Thomas R. Anthony

General Electric Company

Morris Cohen

Massachusetts Institute of Technology

Arthur S. Nowick

Columbia University



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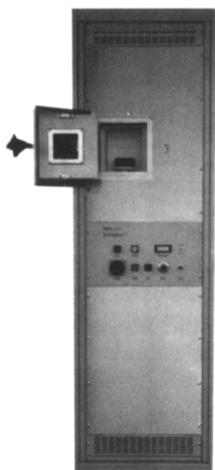
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The 42nd annual meeting of the International Field Emission Society will be held at the University of Wisconsin at Madison from August 6-11, 1995. This is the most widely attended meeting on field emission, ionization, desorption and evaporation phenomena. Relevant technologies which will be covered include:

- Field electron and ion microscopy
- Field ionization mass spectrometry
- Atom probe microanalysis
- Scanning tunneling microscopy
- Liquid metal ion sources
- Vacuum microelectronics
- Field emission electron sources
- Instrumentation

The proceedings of this conference will be published in Applied Surface Science. The deadline for abstracts is May 15, 1995.

For further information please contact:

T.F. Kelly and P.P. Camus
42nd IFES Symposium Co-Chairmen
University of Wisconsin
1500 Johnson Drive
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